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(71) Applicant (*for all designated States except US*): **KONINKLIJKE PHILIPS ELECTRONICS N.V.** [NL/NL]; Groenewoudseweg 1, NL-5621 BA Eindhoven (NL).

(72) Inventors; and

(75) Inventors/Applicants (*for US only*): **RINK, Ingrid, A.** [DE/NL]; c/o Prof. Holstlaan 6, NL-5656 AA Eindhoven (NL). **VROOM, Reinoldus, B., M.** [NL/NL]; c/o Prof. Holstlaan 6, NL-5656 AA Eindhoven (NL).

(74) Agent: **ELEVELD, Koop, J.**; Prof. Holstlaan 6, NL-5656 AA Eindhoven (NL).

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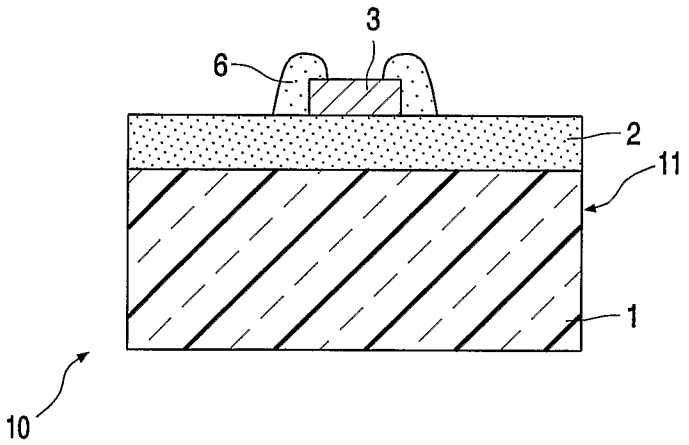
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(54) Title: METHOD OF MANUFACTURING A SEMICONDUCTOR DEVICE AND AN APPARATUS FOR USE IN SUCH A METHOD



(57) Abstract: The invention relates to a method of manufacturing a semiconductor device (10) with a substrate (1) and a semiconductor body (11) which comprises at least one semiconductor element, wherein, after formation of the element, a layer structure is formed which comprises at least one electrically insulating layer (2) or an electrically conductive layer (3), wherein an opening is formed in the layer structure with the aid of a patterned photoresist layer (4) and an etching process, wherein residues are formed on the surface of the semiconductor body (11) during the etching process, and wherein the photoresist layer (4) is ashed, after the etching process, by means of a treatment with an oxygen-containing compound, after which the surface is subjected to a cleaning operation using a cleaning agent comprising a diluted solution of an acid in water and being heated to a temperature above room temperature, thereby causing the residues formed to be removed. According to the invention, sulphuric acid is chosen as the acid for the cleaning agent.

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